

| | Hit s | Search Text | DBs |
|---|----------|--|---|
| 2 | 6 | ((expos\$4 or irradiat\$4 or illuminat\$4) same (pattern\$4 or design) same ((reflective or EUV) near16 (reticle or photomask or mask)) same project\$4) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3) near18 (project\$4 or propagat\$4) near16 (light or illumina\$5)))) and ((wafer or substrate or object) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) and ((mask or reticle or photomask) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 3 | 5 | ((expos\$4 or irradiat\$4 or illuminat\$4) same (pattern\$4 or design) same ((reflective or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3) near18 (project\$4 or propagat\$4) near16 (light or illumina\$5)))) and ((wafer or substrate or object) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) and ((mask or reticle or photomask) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 4 | 16 | ((expos\$4 or irradiat\$4 or illuminat\$4) same (pattern\$4 or design) same ((reflective or EUV) near16 (reticle or photomask or mask))) and ((mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3) near16 (light or illlumina\$7)))) and ((wafer or substrate or object) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) and ((mask or reticle or photomask) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 5 | 11 | ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflective or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3) near16 (light or illlumina\$7)))) and ((wafer or substrate or object) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) and ((mask or reticle or photomask) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 6 | 12 | ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflective or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3) near16 (light or illumina\$7)))) and ((wafer or substrate or object or mask or reticle or photomask) same (driv\$4 or mov\$5 or rotat\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 7 | 77 | ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflective or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object or mask or reticle or photomask) same (driv\$4 or mov\$5 or rotat\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 8 | 72 | ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflective or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) and ((mask or reticle or photomask) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 9 | 18 | ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflect\$4 or EUV) near20 (reticle or photomask or mask)) same (pluralit\$4 or multiple)) and (pattern\$4 same (mask or reticle or photomask) same ((horizontal\$3 near26 vertical\$3) or (X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) and ((mask or reticle or photomask) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4) same adjust\$4 same (angle or tilt))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 10 | 2 | 430/394.ccls. and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflect\$4 or EUV) near20 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((horizontal\$3 near26 vertical\$3) or (X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object) same (stag\$4 or hold\$4) same rotat\$4) and ((mask or reticle or photomask) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4) same adjust\$4 same (angle or tilt)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 11 | 3 | 430/397.ccls. and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflective or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object or mask or reticle or photomask) same (driv\$4 or mov\$5 or rotat\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 12 | 3 | 430/394.ccls. and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflective or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object or mask or reticle or photomask) same (driv\$4 or mov\$5 or rotat\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 13 | 6 | 430/396.ccls. and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflective or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object or mask or reticle or photomask) same (driv\$4 or mov\$5 or rotat\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 14 | 1 | 430/322.ccls. and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflective or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((horizontal\$3 near18 vertical\$3) or (X\$3direction or Y\$3direction or Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object or mask or reticle or photomask) same (driv\$4 or mov\$5 or rotat\$4) same (angle or tilt\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 15 | 13 | 430/322.ccls. and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((reflect\$4 or EUV) near16 (reticle or photomask or mask))) and (pattern\$4 same (mask or reticle or photomask) same ((horizontal\$3 near18 vertical\$3) or (X\$3direction or Y\$3direction or Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object or mask or reticle or photomask) same (driv\$4 or mov\$5 or rotat\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 16 | 73 | ((expos\$4 or irradiat\$4 or illuminat\$4) same (reticle or photomask or mask) same ((ion near9 beam) or e\$3beam or (electron near5 beam))) and (pattern\$4 same (mask or reticle or photomask) same ((X\$3direction near17 Y\$3direction near19 Z\$3direction) or (parallel near18 (perpendicular or orthogonal\$3)))) and ((wafer or substrate or object) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) and ((mask or reticle or photomask) same (stag\$4 or hold\$4) same (driv\$4 or mov\$5 or rotat\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |